

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

TRAINTE the Application of Steinberg

Application No.: 10/076,858

Attorney Docket No.: R&H 03-19; ACT 183/184; DN: 51969

Filed:

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Examiner: Stephen J. Stein

Group Art Unit: 1775

CERTIFICATE OF MAILING UNDER 37 C.F.R § 1.8(a)

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Cristin Donahue

Commissioner for Patents Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

UNDER 37 C.F.R. § 1.97
In compliance with the duty of disclosure set forth in 37 C.F.R. § 1.56, Applicants are submitting herewith a Form PTO-1449 and a copy of the references listed thereon. This Information Disclosure Statement is being filed with a Request for Continued Examination. Accordingly, there is no fee required under.

Applicants respectfully request full and proper consideration of the listed information during examination of the application, and that the listed information be printed on any patent that issues therefrom.

Respectfully submitted.

DANN, DORFMAN, HERRELL & SKILLMAN A Professional Corporation

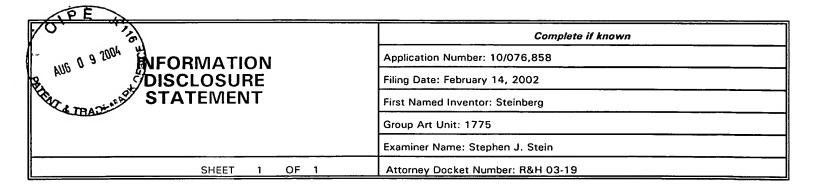
Attorneys for Applicant(s)

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Telephone: (215) 563-4100 Facsimile: (215) 563-4044 Enclosures - Form PTO-1449

Copies of References listed on PTO -1449



UNITED STATES PATENT DOCUMENTS					
EXAMINER'S INITIALS	CITE NO.	PATENT NUMBER	ISSUE DATE MM-DD-YYYY	FIRST NAMED INVENTOR	
		4810557	03/07/1989	Blonder	
		4837129	06/06/1989	Frisch et al.	
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FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	CITE NO.	DOCUMENT NUMBER	COUNTRY OR REGION	DATE OF PUBLICATION MM-DD-YYYY	FIRST NAMED INVENTOR OR APPLICANT		
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OTHER PRIOR ART - NON-PATENT DOCUMENTS				
EXAMINER'S CITE Inc. NO. jou put		Include name of the author (in Capital Letters), title of the article (when appropriate), title of the item(book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published		
		Nijdam, et al. "Etching of silicon in alkaline solutions: a crtical look at the {111} minimum," MESA		
		Oosterbroek, et al. "New design methodologies in <111> oriented silicon wafers," MESA		
		Suchtelen, et al. "Simulation of Anisotropic Wet-Chemical Etching Using a Physical Model," MESA		

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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP §609. Draw a line through citation if citation not in conformance and reference not considered. Include a copy of this form with next communication to applicant.